

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S5	428	((UHV or ultra adj high adj vacuum) same (CVD or chemical adj vapor adj deposit\$4) or UHV\$1CVD) and (treat\$4 or clean\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/18 18:49
S67	945	((UHV or ultra adj high adj vacuum) near5 (CVD or chemical adj vapor adj deposit\$4) or UHV\$1CVD)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/18 18:50
S68	11	((UHV or ultra adj high adj vacuum) near5 (CVD or chemical adj vapor adj deposit\$4) or UHV\$1CVD) same (wafer or substrate) near2 (boat or jig or holder or carrier)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/18 18:52
S69	2	"20030070608".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/18 18:54
S70	7	("5181964" "5607511" "5297452" "5906680").pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/18 18:55
S71	22	(uhv\$1cvd or ultra near2 high near2 vacuum near10 (cvd or chemical near2 vapor)) same batch	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/18 18:58
S74	63	wafer near2 (holder boat jig carrier).ti. and batch near2 process\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/18 19:00
S73	5687	wafer near2 (holder boat jig carrier).ti.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/18 19:00
S72	14	(uhv\$1cvd or ultra near2 high near2 vacuum near10 (cvd or chemical near2 vapor)) same horizont\$5	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/18 19:00

S76	1	wafer near2 (holder boat jig carrier).ti. and (uhv or ultra near2 high near2 vacuum)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/18 19:01
S75	4741	wafer near2 (holder boat jig carrier).ti. and uhv or ultra near2 high near2 vacuum	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/18 19:01
S78	5	"5217501".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/18 19:12
S77	166	wafer near2 (holder boat jig carrier) and (uhv or ultra near2 high near2 vacuum)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/18 19:12
S79	63	(UHV or ultra adj high adj vacuum same (CVD or chemical adj vapor adj deposit\$4)) same vertical	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/22 16:57
S80	99	batch near10 wafer same boat near10 (horizont\$6 or vertical\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/22 16:59
S81	3	batch near10 wafer same boat near10 (horizont\$6 or vertical\$4) and (uhv or ultra near2 high)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/22 17:02
S82	47	(uhv or ultra near2 high) same (cvd or chemical near2 vapor near2 deposit\$4) same (vertical\$5 or horizont\$7)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/22 17:10
S83	26	(uhv or ultra near2 high) same (cvd or chemical near2 vapor near2 deposit\$4) same batch	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/22 17:22
S84	2	"5181964".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/23 14:28

S85	934	(uhv or ultra near2 high near2 vacuum) near10 (cvd or chemical near2 vapor near2 deposit\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/23 14:30
S89	9	S87 and (vacuum near2 ultra near2 high or uhv)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/23 14:35
S88	16	S87 and vacuum	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/23 14:35
S87	17	(hans near2 buschbeck or philipp near2 bartholet or siegfried near2 wiltsche or jurgen near2 ramm).in	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/23 14:35
S86	1	(uhv or ultra near2 high near2 vacuum) near10 (cvd or chemical near2 vapor near2 deposit\$4) near15 cluster	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/23 14:36
S90	5	(uhv or ultra near2 high near2 vacuum) near10 (cvd or chemical near2 vapor near2 deposit\$4) same cluster	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/23 15:11
S91	2	"0894332"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/23 15:12
S93	333	quartz near2 liner	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/23 15:45
S92	10	"894332"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/23 15:45
S94	91	quartz near10 liner same reactor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/23 15:48

S96	2893	liner near10 uniform\$6	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/23 15:53
S95	78	double near2 wall same (cvd or chemical near2 vapor near2 deposit\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/23 15:53
S97	7	quartz near5 liner near10 uniform\$6	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/23 15:56
S98	32	(chemical near2 vapor near2 deposit\$4 or cvd) same interior near4 atmosphere	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/23 15:57
S99	2056	wafer near2 (boat or jig or holder) near10 heat\$6	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/01 18:04
S100	634	wafer near2 (boat or jig or holder) near10 heat\$6 and cvd	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/01 18:08
S101	91	wafer near2 (boat or jig or holder) near10 heat\$6 near5 element	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/02 12:03
L2	17	(sensor or thermo\$1couple) near15 (wafer or substratee) near5 (boat or jig or holder) near10 vertical	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/02 12:04
L1	531	(sensor or thermo\$1couple) near15 (wafer or substratee) near5 (boat or jig or holder)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/02 12:04
L3	103	(thermo\$1couple) near15 (wafer or substratee) near5 (boat or jig or holder)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/02 12:05

L4	36	(thermo\$1couple) near15 (wafer or substratee) near5 (boat or jig or holder) and batch\$6	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/02 12:30
L5	9	plasma near10 clean\$6 near10 ev	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/02 12:53
L7	3736	temperature near2 control\$7 near10 control\$6 near10 loop	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/02 12:54
L6	6660	temperature near10 control\$7 near10 control\$6 near10 loop	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/02 12:54
L9	1	temperature near2 control\$7 near10 control\$6 near10 loop same (wafer or substrate) near10 batch\$6	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/02 12:56
L8	75	temperature near2 control\$7 near10 control\$6 near10 loop and (wafer or substrate) near10 batch\$6	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/02 12:56
L10	12	temperature near2 control\$7 near10 control\$6 near10 loop near10 (negative or feed\$1back) and (wafer or substrate) near10 batch\$6	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/02 12:57
L13	315	temperature near10 control\$6 near10 loop near10 (negative or feed\$1back) same (wafer or substrate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/02 12:58
L12	725	temperature near10 control\$6 near10 loop near10 (negative or feed\$1back) and (wafer or substrate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/02 12:58
L11	2011	temperature near10 control\$6 near10 loop near10 (negative or feed\$1back)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/02 12:58

L14	55	temperature near10 control\$6 near10 loop near10 (negative or feed\$1back) same (wafer or substrate) and batch	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/02 14:32
L15	145	temperature near10 control\$6 near10 loop near10 (negative or feed\$1back) same (wafer or substrate) and Cvd	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/02 14:44
L16	45	temperature near10 control\$6 near10 loop near10 (negative or open) same (wafer or substrate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/02 14:45